



¹¹B in the form of Boron Trifluoride Gas

Description

Boron trifluoride gas is the ideal silicon wafer dopant for the production of highly integrated, high-density microchips. ¹¹B_F₃ provides for greater efficiency and increased production throughput, and helps to make chips smaller and better.

Physical Properties:

Material	11B - Boron-11 in the form of Boron Trifluoride Electronic Grade
Enrichment	11B > 99,9 at%

Chemical Properties

Form	BF ₃
Purity	> 99,9 wt%

Impurities in vppm

Ar+O ₂	5
CO ₂	10
HF	5
N ₂	5
SiF ₄	25
SO ₂	10